

discharging from said discharging electrode;

an output window for partially reflecting the laser light and for outputting a portion of the laser light amplified between said total reflection mirror and said output window;

a blower for circulating the laser gas within said chamber, so that the laser gas passing an electrical discharging region of said discharging electrode is circulated in said chamber and is returned to the electrical discharging region of said discharging electrode; and

operating means for operating said blower in accordance with a state of the electrical discharging from said discharging electrode, including first means for operating the blower rotation in a stand-by state in which no laser gas is excited by the electrical discharging from said discharging electrode and thus no laser light is emitted whereas the gas laser device is in a condition to output the laser light, and second means for operating the blower rotation in an in-operation state in which the laser gas is excited by the electrical discharging from said discharge electrode and the laser light is being outputted.

F1
level

2. A gas laser device according to Claim 1, wherein said first means operates rotation of said blower when said gas laser device is in the stand-by state by stopping the blower.

4. A gas laser device according to Claim 2, wherein said blower has a blowing blade rotatably supported within said chamber.

F2

5. A gas laser device according to Claim 1, wherein said laser device comprises a noble gas halide excimer laser.

6. A gas laser device according to Claim 5, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

7. A gas laser device according to Claim 1, further comprising an exposure apparatus for exposing a substrate to the laser light supplied from said gas laser device.

F2
Lined

8. A gas laser device according to Claim 7, wherein said first means operates rotation of said blower when said gas laser device is in the stand-by state by stopping the blower.

10. A gas laser device according to Claim 8, wherein said blower has a blowing blade rotatably supported within said chamber.

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11. A gas laser device according to Claim 8, wherein said laser device comprises a noble gas halide excimer laser.

12. A gas laser device according to Claim 11, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

13. An exposure apparatus, comprising:
a laser light source having (i) a chamber for sealingly storing a laser gas therein, (ii) a discharging electrode for exciting the laser gas through electrical discharging, (iii) a total reflection mirror for totally reflecting laser light produced by the electrical discharging from said discharging electrode, (iv) an output window for partially reflecting the laser light and for outputting a portion of the laser light reflected between said total reflection mirror and said output window, and (v) a blower for circulating the laser gas within said chamber so that the laser gas passing an electrical discharging region of said discharging electrode is circulated in said chamber and is returned to the electrical discharging region of said discharging electrode;
a main assembly for exposing a substrate to the laser light from said laser light source;
and

F3 would
operating means for operating said blower in accordance with a state of electrical discharging of said discharging electrode including first means for operating rotation of the blower in a non-exposure-operating state in which no laser gas is excited by the electrical discharging from said discharging electrode and thus no laser light is emitted whereas the exposure device is in a condition to output the laser light, and second means for operating rotation of the blower in an exposure state in which the laser gas is excited by electrical discharging from said discharging electrode and the laser light is being outputted.

14. An apparatus according to Claim 13, wherein said operating means further comprises means for increasing a rotation speed of said blower in response to a start of an exposure job in which the exposure operation is performed through said main assembly.

15. An apparatus according to Claim 14, wherein said operating means stops the revolution of said blower before a start of the exposure job.

17. An apparatus according to Claim 15, wherein said blower has a blowing blade rotatably supported within said chamber.

F4
18. An apparatus according to Claim 13, wherein said laser light source comprises a noble gas halide excimer laser.

19. An apparatus according to Claim 18, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

20. A semiconductor device manufacturing method comprising:
sealingly storing a laser gas in a chamber;
exciting, using a discharging electrode, the laser gas through electrical discharge;
totally reflecting laser light produced by the electrical discharging from said
discharging electrode by a total reflection mirror;
partially reflecting the laser light by an output window and outputting a portion of the
laser light reflected between said total reflection mirror and said output window;
circulating, using a blower, the laser gas within the chamber, so that the laser gas
passing an electrical discharging region of the discharging electrode is circulated in the
chamber and is returned to the electrical discharging region of the discharging electrode; and
operating rotation of the blower in accordance with a state of electrical discharging
from said discharging electrode including operating rotation of the blower in a stand-by state
in which no laser gas is excited by the electrical discharging from said discharging electrode
and thus no laser light is emitted whereas the chamber is in a condition to output the laser
light, and differently operating rotation of the blower in an in-operation state in which the
laser gas is excited by the electrical discharging from said discharge electrode and the laser
light is being outputted.

21. A gas laser device according to Claim 1, wherein said laser device comprises an F_2
laser.

22. A gas laser device according to Claim 5, wherein said noble gas halide excimer
laser comprises a KrF excimer laser.

23. A gas laser device according to Claim 5, wherein said noble gas halide excimer
laser comprises an ArF excimer laser.

24. A gas laser device according to Claim 8, wherein said laser device comprises an F₂ laser.

25. A gas laser device according to Claim 11, wherein said noble gas halide excimer laser comprises a KrF excimer laser.

26. A gas laser device according to Claim 11, wherein said noble gas halide excimer laser comprises an ArF excimer laser.

F₂ laser
27. An apparatus according to Claim 13, wherein said laser light source comprises an F₂ laser.

28. An apparatus according to Claim 18, wherein said noble gas halide excimer laser comprises a KrF excimer laser.

29. An apparatus according to Claim 18, wherein said noble gas halide excimer laser comprises an ArF excimer laser.

Please add New Claims 21-46 as follows:

Rule 121
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--21. A gas laser device, comprising:
a chamber for sealingly storing a laser gas therein;
a discharging electrode for exciting the laser gas through electrical discharging;
a blower for circulating the laser gas within said chamber, so that the laser gas passing an electrical discharging region of said discharging electrode is circulated in said chamber and is returned to the electrical discharging region of said discharging electrode; and

operating means for operating said blower in accordance with a state of the electrical discharging from said discharging electrode, including first means for operating the blower rotation in a stand-by state in which no laser gas is excited by the electrical discharging from said discharging electrode and thus no laser light is emitted whereas the gas laser device is in a condition to output the laser light, and second means for operating the blower rotation in an in-operation state in which the laser gas is excited by the electrical discharging from said discharge electrode and the laser light is being outputted.

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22. A gas laser device according to Claim 21, wherein said first means operates rotation of said blower when said gas laser device is in the stand-by state by stopping the blower.

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23. A gas laser device according to Claim 22, wherein said blower has a blowing blade rotatably supported within said chamber.

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24. A gas laser device according to Claim 21, wherein said laser device comprises a noble gas halide excimer laser.

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25. A gas laser device according to Claim 24, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

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26. A gas laser device according to Claim 21, further comprising an exposure apparatus for exposing a substrate to the laser light supplied from said gas laser device.

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27. A gas laser device according to Claim 26, wherein said first means operates rotation of said blower when said gas laser device is in the stand-by state by stopping the blower.

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28. A gas laser device according to Claim 27, wherein said blower has a blowing blade rotatably supported within said chamber.

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29. A gas laser device according to Claim 27, wherein said laser device comprises a noble gas halide excimer laser.

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30. A gas laser device according to Claim 29, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

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40 30
31. A gas laser device according to Claim 29, wherein said laser device comprises an F₂ laser.

41 33
32. A gas laser device according to Claim 29, wherein said noble gas halide excimer laser comprises a KrF excimer laser.

42 33
33. A gas laser device according to Claim 29, wherein said noble gas halide excimer laser comprises an ArF excimer laser.

43 34
34. A gas laser device according to Claim 27, wherein said laser device comprises an F₂ laser.

35. A gas laser device according to Claim 29, wherein said noble gas halide excimer laser comprises a KrF excimer laser.

36. A gas laser device according to Claim 29, wherein said noble gas halide excimer laser comprises an ArF excimer laser.

37. An exposure apparatus, comprising:
a laser light source having (i) a chamber for sealingly storing a laser gas therein, (ii) a discharging electrode for exciting the laser gas through electrical discharging, and (iii) a blower for circulating the laser gas within said chamber so that the laser gas passing an electrical discharging region of said discharging electrode is circulated in said chamber and is returned to the electrical discharging region of said discharging electrode;
a main assembly for exposing a substrate to the laser light from said laser light source;
and
operating means for operating said blower in accordance with a state of electrical discharging of said discharging electrode including first means for operating rotation of the blower in a non-exposure-operating state in which no laser gas is excited by the electrical discharging from said discharging electrode and thus no laser light is emitted whereas the exposure device is in a condition to output the laser light, and second means for operating rotation of the blower in an exposure state in which the laser gas is excited by electrical discharging from said discharging electrode and the laser light is being outputted.

38. An apparatus according to Claim 37, wherein said operating means further comprises means for increasing a rotation speed of said blower in response to a start of an exposure job in which the exposure operation is performed through said main assembly.

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39. An apparatus according to Claim 38, wherein said operating means stops the revolution of said blower before a start of the exposure job.

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40. An apparatus according to Claim 39, wherein said blower has a blowing blade rotatably supported within said chamber.

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41. An apparatus according to Claim 37, wherein said laser light source comprises a noble gas halide excimer laser.

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42. An apparatus according to Claim 41, wherein said noble gas halide excimer laser comprises an XeCl excimer laser.

75 cont 52 46
43. An apparatus according to Claim 37, wherein said laser light source comprises an F₂ laser.

53 50
44. An apparatus according to Claim 41, wherein said noble gas halide excimer laser comprises a KrF excimer laser.

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45. An apparatus according to Claim 41, wherein said noble gas halide excimer laser comprises an ArF excimer laser.

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46. A semiconductor device manufacturing method comprising:
sealingly storing a laser gas in a chamber;
exciting, using a discharging electrode, the laser gas through electrical discharge;
circulating, using a blower, the laser gas within the chamber, so that the laser gas passing an electrical discharging region of the discharging electrode is circulated in the